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Supplementary Materials for

Layer-engineered large-area exfoliation of graphene

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Note S1 Figs. S1 to S14 References

note S1. Raman analysis

We can extract the contributions of the strain and doping effect for a given point with the analysis method proposed by LEE et al (26). The model consists of two vectors: $OP=ae_T + be_H$, where a and b are constants, and e_T and e_H are unit vector components for tensile strain and hole doping effects, respectively (here, the initial values of $e_T = 2.2$ and $e_H = 0.7$ were used). We assumed that the intrinsic frequencies of the G and 2D peaks of 1582 cm⁻¹ and 2677 cm⁻¹, respectively, were not affected by extra charge and strain. Note that we cannot observe a clear linearity caused by charge doping (0.75 for holes and 0.44 for electrons) in graphene prepared by Au-LEE. Therefore, we conclude that the linear variations in ω_G and ω_{2D} are due to the native strain in graphene.

Supplementary Figures





Fig. S1 OM images of Au-LEE-graphene. Twenty-four samples of large-area monolayer graphene produced by the LEE method on 300 nm SiO₂/Si substrates. The average size of exfoliated graphene is similar to that of the atomically flat domains of the mother graphite, as shown in Fig. 1 and fig. S2. Most of the cracks in exfoliated graphene existed at the domain boundaries because transferred LEE-graphene could not conformally contact with target substrate. Therefore, we believe that the size of exfoliated graphene could be even larger and crackless, towards the wafer scale, if we prepare large-scale and flat graphite on rigid substrate (e.g., CVD-grown multilayer graphene on wafer).



Fig. S2 OM images of the cleaved natural graphite surface. The size and area of individual domain is analogous to those of LEE-graphene. The calculated areas of flat domains are written on the top left in each image.



Fig. S3 Non-spalling area on the surface of Au film. (A) Surface-OM image of the exfoliated Au film from natural graphite. (B) Raman mapping image is overlaid onto the white box in (A). The purple areas indicates the presence of graphene. Individual spectrum was acquired with 40 μ m steps along the X- and Y-axis. (C) Representative Raman spectra of the exfoliated Au film with graphene (red) or without graphene (black).



Fig. S4 Surface morphology of HOPG. To analyze the surface morphology of HOPG, we used OM (both bright field (BF) and dark field (DF) modes) and AFM. (**A-C**) The surface of HOPG consists of large domains with lateral sizes of 1-2 mm or more, but each domain consists of step edges that naturally occur during mechanical cleavage. These step edges consist of 1-3 layers and are aligned in one direction according to AFM analysis. The root mean square value of the HOPG surface was measured to be 0.42 nm. (**D**) As a result of applying the LEE method to HOPG flakes, a discontinuous monolayer is obtained over the entire area, and bi- and tri-layers are also present because crack propagation easily occurs at the step edges present in HOPG.



Fig. S5 Monolayer coverage of LEE-graphene. (A-C) Representative OM images of LEEgraphene 1 x 1.5 mm² and 1 x 1 mm² in size and corresponding images in which the region of monolayer (ML) graphene is filled in red color. (D) Calculated optical contrast difference (C_D) of monolayer graphene (C_{ML}) with respect to the 300 nm SiO₂/Si substrate (C_S), which is approximately -4.7. Each pixel corresponding to monolayer graphene is marked in red in (A-C). (E) The coverage of monolayer graphene is calculated to be 43%, 58% and 35%.



Fig. S6 Monolayer coverage for standard exfoliation. (A) OM image of an approximately 1 mm² area after standard exfoliation. Monolayer graphene exists in the dashed circular regions in the optical image. (B) High-magnification OM images of the circular regions. The size of individual monolayer graphene is also denoted in the images.



Fig. S7 Schematic illustration of the spalling path depending on the metal film. (A-D) As the increase of binding energy between metal and graphene, the spalling depth increase.



Fig. S8 hBN encapsulation process and Raman spectrum before/after encapsulation. (A-D) Monolayer graphene was prepared by the LEE method. The top hBN flake was dropped onto monolayer graphene, and the hBN/graphene stack was lifted up at 60 °C. Subsequently, we dropped the hBN/graphene stack onto the bottom hBN flake at 130 °C. (E) Representative Raman spectrum of monolayer graphene before and after encapsulation.



Fig. S9 Another data set of Raman spectroscopy. ω_{2D} versus ω_G recorded on two different samples: prepared by Au-LEE (red circles) and hBN encapsulation (blue circles).



Fig. S10 Raman intensity mapping of LEE-graphene. Raman intensity mapping of the D peak (1350 cm⁻¹), G peak (1580 cm⁻¹) and 2D peak (2700 cm⁻¹) of monolayer graphene obtained by Au-LEE.



Fig. S11 XPS analysis of LEE-graphene. (A-C) Core-level peaks of Au 4f, K 2p and I 3d in the XPS spectrum of monolayer graphene obtained by Au-LEE. Peaks related to the Au and Au etchants (KI/I₂ solution) are not observed, which indicates that the stressor Au film was completely removed and that chemical residues from the Au etchant were fully washed away.



Fig. S12 Repeated exfoliation of large-area monolayer graphene. (A) Schematic illustration of the repeated LEE process. (**B-D**) Optical images of the large-area monolayer graphene on 300 nm-SiO₂/Si wafers obtained by the first, second, and third repeated LEE processes. (**E**) Raman spectra of three different graphene layers exfoliated from the same graphite flake.



Fig S13. Layer engineered exfoliation for hBN. (A) OM image of hBN crystals. (B and C) OM images of layer-engineered hBN prepared by using Pd and Co. Interfacial toughness with hBN is ~170 meV and ~350 meV, respectively. Insets show that the thickness of each exfoliated hBN we obtained is 1.5 nm and 16 nm, respectively, with a lateral size of a few hundred μ m (42).



Fig. S14. Raman spectra of LEE-graphene before and after soaking treatment. The etchant related peaks are observed from LEE-graphene without soaking treatment (black) at lower wavelength region (110 and 160 cm⁻¹) which represent triiodide (I_3^-) and pentaiodide (I_5^-) but it disappeared from the LEE-graphene with soaking treatment (red) (43).

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